

LPE SEPARATE CONFINEMENT InGaAsP/GaAs AND
InGaAsP/InP DH LASERS WITH VERY LOW THRESHOLD

Zh.I.Alferov, D.Z.Garbuzov and I.N.Arsent'ev

A.F.Ioffe Physical-Technical Institute, USSR Academy of
Sciences, Leningrad, USSR

It has been shown in [1,2] that DH laser with the active region thickness $d_a \approx 0.02 \mu\text{m}$ can be prepared in a rotating variant of LPE. However, in these works the decrease of threshold current densities (I_{th}) in comparison with those typical to DH lasers with $d_a \approx 0.2 \mu\text{m}$ was not obtained. In [3] with a method of liquid epitaxy, InGaAsP/InP DH lasers ($\lambda = 1.3 \mu\text{m}$) with separate confinement (SC) were fabricated with threshold for samples with four facets cleaved 512 A/cm at $d_a = 0.05 \mu\text{m}$. This paper reports for the first time on the fabrication of low-threshold SC InGaAsP/GaAs LPE DH lasers ($I_{th} = 260 \text{ A/cm}^2$, $\lambda = 0.85-0.79 \mu\text{m}$) as well as on the achievement of threshold 300 A/cm^2 in similar SC InGaAsP/InP DH lasers ($\lambda = 1.25 \mu\text{m}$).

The calculations performed show that the reason for I_{th} to decrease with d_a decreasing in SC DH lasers may be the following: 1) the decrease of the threshold current component required to reach the inverse population; 2) the decrease of absorption losses in the active region especially significant in case of narrow-band gap InGaAsP/InP DH lasers. However, in narrow band lasers with d_a decreasing a relative role of Auger recombination increases and hence optimum values of d_a for these lasers may appear larger than for the wide-band gap InGaAsP/GaAs DH lasers.

The both types of laser structures described above were prepared by a usual LPE method in a modified sliding boat providing to produce InGaAsP layers of the given composition and doping, with thickness from 0.02 to $1 \mu\text{m}$. Optimum parameters of laser structures were defined in the experiments on photopumping of isotype SC DH structures using a number of pulsed and continuous lasers (Nd^{+3} , Ar^{+} - and Kr^{+} - lasers). For SC InGaAsP/InP DH in accordance with the data [3] minimum values of I_{th} were obtained in the structures with $d_a \approx 0.06 \mu\text{m}$ and total thickness of both waveguide layers $d \approx 0.4 \mu\text{m}$. P-n junction in these structures was produced by Zn diffusion to isotype N-n-N structure. The position of p-n junction coincided with the heteroboundary between up-

per InP-emitter and InGaAsP-waveguide layer. The lowest value of threshold current density in four facets cleaved lasers was 300 A/cm^2 . Minimum threshold current was 25-30 mA.

In case of InGaAsP/GaAs DH, wide band emitters were made of n- and p-In_{0.49}Ga_{0.51}P doped by Zn and Te during the growth process. Undoped In_{0.25}Ga_{0.75}As_{0.52}P_{0.48} waveguide layers and InGaAsP-active region have band gaps 1.7 and 1.43 - 1.57 eV, correspondingly. Lasers with best parameters were fabricated from the structure with $d_a = 0.02 \text{ }\mu\text{m}$. For four facets cleaved samples minimum I_{th} was equal to 260 A/cm^2 , and for usual broad-area lasers with cavity length $L=500 \text{ }\mu\text{m}$, the smallest I_{th} was 530 A/cm^2 . Threshold currents in samples of $L \geq 300 \text{ }\mu\text{m}$ were small enough (as in case of four facets cleaved InGaAsP/InP lasers mentioned above) to obtain a continuous wave operation for broad-area samples. In the laser of $310 \times 140 \text{ }\mu\text{m}$ the emitting power per one mirror at $I = 1 \text{ A}$ was 77 mW. In diodes with $L < 500 \text{ }\mu\text{m}$ I_{th} increased linearly with $1/L$; differential quantum efficiency (η_d) increased with $1/L$ in the same samples. For a laser with $L = 300 \text{ }\mu\text{m}$ η_d was 25% per one mirror within the interval $(1.2-2.5) I_{th}$. Emission pulse power with pulse duration 100 nsec at $I = 2.5 I_{th}$ was equal to 0.5 W and the total efficiency of electrical to light power conversion per two mirrors was 20%.

References

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